

TI - Photosensitive resin compositions having end groups of

(methano)cyclohexene skeleton

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CC - 37-6 (Plastics Manufacture and Processing)

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FAN.CNT 1

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PR - JP 1999-74373 19990318

AB - The compns., useful for coatings, sealing materials, adhesives, binder etc., comprise (A) compds. having .gtoreq.2 (/mol.) (methano)cyclohexe skeletons, (B) vinyl ether monomers, and (C) photopolymn. initiators, where .gtoreq.1 of the (methano)cyclohexene moiety exists at mol. terminals of A. The compns. show excellent curability in air and prov cured products with good gloss and strong adhesion to supports. Thus, parts 3,6-methano-4-cyclohexene-1,2-dicarboxylic acid was reacted with OH-terminated polybutadiene (Poly bdr 45M) at 110.degree. in the prese of Et3NCl to give a modified polybutadiene (A1), 50 parts of A1 was blended with 50 parts triethylene glycol divinyl ether and 3 parts Irgacure 261 to give a photocurable compn. The compn. was applied on glass substrate and lost surface tack upon 70 mJ/cm2 UV exposure. The cured film of the compn. showed good adhesion to steels, plastics, and plywoods.

ST - methanocyclohexene terminated photosensitive compn coating binder; methanocyclohexenecarboxylic acid vinyl ether photosensitive compn; adhesion gloss tackfree property photosensitive compn

IT - Polymerization catalysts
(cationic, photochem.; photosensitive resin compns. having end group of (methano)cyclohexene end groups)

IT - Butadiene rubber, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(hydroxy-terminated, Poly bd-R 45M, reaction products with 3,6-methano-4-cyclohexene-1,2-dicarboxylic acid and triethylene gly divinyl ether; photosensitive resin compns. having end groups of (methano)cyclohexene end groups)

IT - Light-sensitive materials
(photosensitive resin compns. having end groups of (methano)cyclohe end groups)

IT - Polyimides, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photosensitive resin compns. having end groups of (methano)cyclohe end groups)

IT - Polyimides, preparation
Polyimides, preparation
Polyimides, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or

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Cl 1, 2, 9, 10, 13, 17, 19, 20-29